

Resource Summary Report

Generated by [RRID](#) on Aug 8, 2026

Rigaku: EUV Optics

RRID:SCR_020436

Type: Tool

Proper Citation

Rigaku: EUV Optics (RRID:SCR_020436)

Resource Information

URL: <https://www.rigaku.com/products/optics/euv>

Proper Citation: Rigaku: EUV Optics (RRID:SCR_020436)

Description: Multilayer optics for extreme UV lithography patterning of semiconductor wafers. High efficiency multilayer optics for 13.5 nm, 6.x nm wavelengths.

Resource Type: instrument resource

Keywords: Rigaku, X-Ray Optics, Instrument Equipment, USEDit,

Availability: Commercially available

Resource Name: Rigaku: EUV Optics

Resource ID: SCR_020436

Alternate IDs: Model_Number_EUV

Record Creation Time: 20220129T080350+0000

Record Last Update: 20260801T190647+0000

Ratings and Alerts

No rating or validation information has been found for Rigaku: EUV Optics.

No alerts have been found for Rigaku: EUV Optics.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.